

# Phase Separation of Dirac Electrons in Topological Insulators at the Spatial Limit

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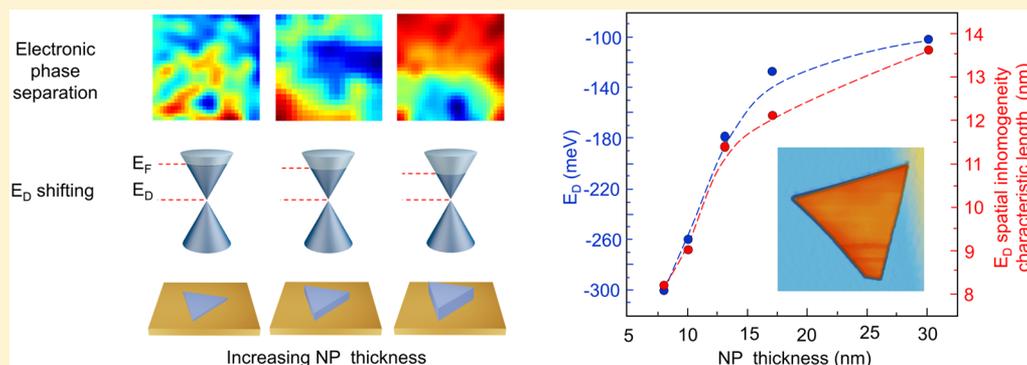
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**S** Supporting Information



**ABSTRACT:** In this work we present unique signatures manifested by the local electronic properties of the topological surface state in  $\text{Bi}_2\text{Te}_3$  nanostructures as the spatial limit is approached. We concentrate on the pure nanoscale limit (nanoplatelets) with spatial electronic resolution down to 1 nm. The highlights include strong dependencies on nanoplatelet size: (1) observation of a phase separation of Dirac electrons whose length scale decreases as the spatial limit is approached, and (2) the evolution from heavily n-type to lightly n-type surface doping as nanoplatelet thickness increases. Our results show a new approach to tune the Dirac point together with reduction of electronic disorder in topological insulator (TI) nanostructured systems. We expect our work will provide a new route for application of these nanostructured Dirac systems in electronic devices.

**KEYWORDS:** Topological insulator nanostructures,  $\text{Bi}_2\text{Te}_3$ , Dirac electrons, scanning tunneling spectroscopy, phase separation, doping

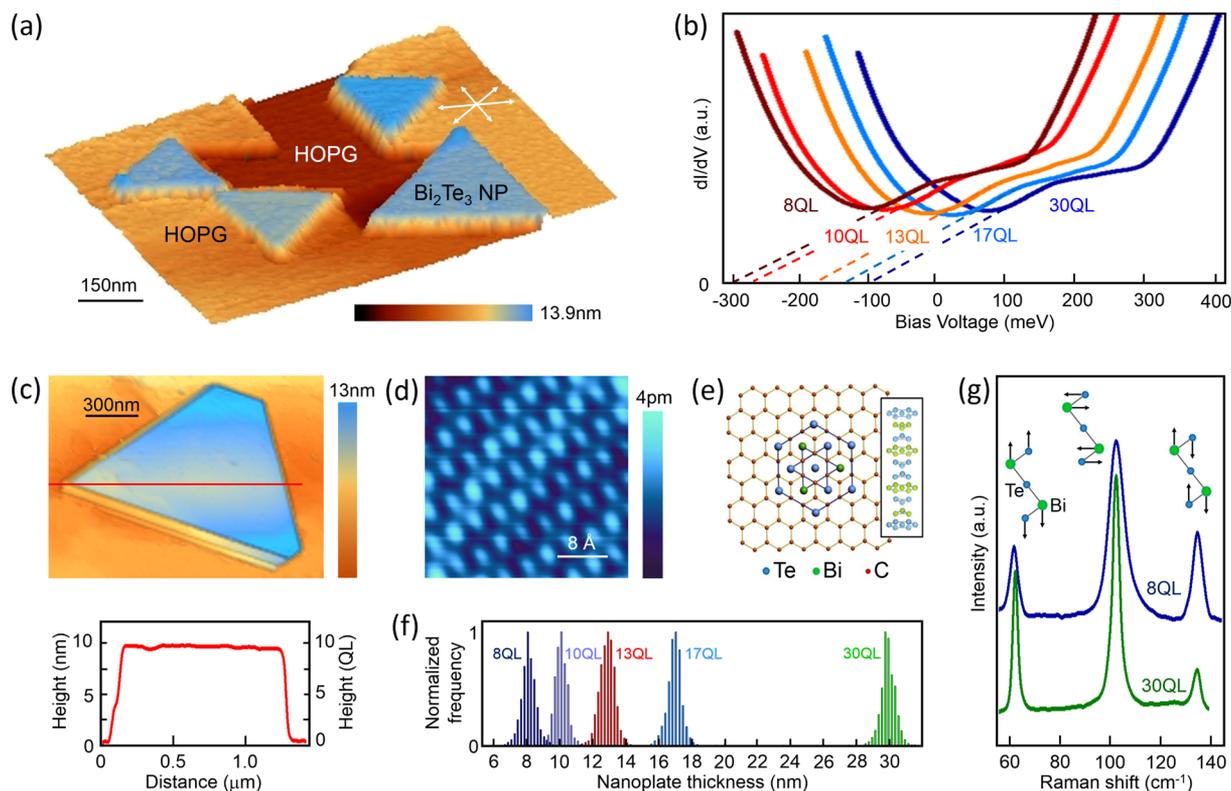
Recently both theoretical predictions and experimental measurements have demonstrated that  $\text{Bi}_2\text{Te}_3$ , a layered binary compound, is a three-dimensional (3D) topological insulator (TI), a new state of quantum matter with a bulk gap and massless Dirac surface states topologically protected with helical spin texture.<sup>1</sup>

The Fermi level in 3D TIs does not necessarily coincide with the Dirac point. In some of these materials, the Fermi level falls

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**Figure 1.** Structure and morphology of  $\text{Bi}_2\text{Te}_3$  nanoplatelets. (a) STM image of a group of  $\text{Bi}_2\text{Te}_3$  NPs grown on HOPG,  $V_S = 0.5$  V,  $I = 1.0$  pA. Nanoplatelets (in blue) with uniform thicknesses were aligned in the same orientation on the graphite layer (white arrows), an unequivocal sign of epitaxial growth. (b) Representative specs for  $\text{Bi}_2\text{Te}_3$  NPs of five different thicknesses where a shift in Dirac energy was observed with respect to Fermi level. (c) Constant-current STM image of a triangular  $\text{Bi}_2\text{Te}_3$  nanoplatelet grown on HOPG;  $V_S = 1$  V,  $I = 1.0$  pA, where  $V_S$  is the sample bias voltage with respect to the sample and  $I$  is the tunneling current (lower panel). Line profile along the red linecut shows that NP is 10 QL ( $\sim 10$  nm) in height and has a base length of  $1.4 \mu\text{m}$ . (d) Atomically resolved STM image of  $\text{Bi}_2\text{Te}_3$  nanoplatelet showing a lattice constant of  $4.3 \pm 0.3$  Å. (e) Diagram showing final configuration for van der Waals epitaxial growth mode of  $\text{Bi}_2\text{Te}_3$  on HOPG. Graphite exhibits a honeycomb lattice structure with C–C bond length of  $\sim 1.42$  Å and  $\text{Bi}_2\text{Te}_3$  with rhombohedral structure and a lattice constant of  $4.38$  Å. Lattice mismatch between substrate and  $\text{Bi}_2\text{Te}_3$  is  $\sim 2.7\%$ . (f) Height histogram for NPs used in the current study. (g) Raman spectra from as-grown 8 QL and 30 QL  $\text{Bi}_2\text{Te}_3$  nanoplatelets with corresponding active Raman modes.

in either the conduction band or the valence band, and its position can strongly vary because of naturally occurring defects. In addition, a high density of charge carriers in their bulk generally mixes together bulk and surface transport characteristics. In order to separately access the remarkable properties of the surface carriers in TIs, it is vital to controllably suppress the bulk conductivity by constraining the Fermi level to the bulk bandgap.<sup>2</sup>

This limitation has triggered an intense search for clean TIs with the Fermi level occurring within the gap. One approach is controlling bulk carrier concentration by using an effective compensation dopant like Sn,<sup>3,4</sup> Cd,<sup>4,5</sup> Ca,<sup>6–8</sup> Pb,<sup>9</sup> Na,<sup>10</sup> or Sb.<sup>11,12</sup> However, a high dopant concentration can also introduce undesirable impurity scattering. The Fermi level in TIs can also be manipulated via gating,<sup>13–15</sup> structural deformation,<sup>15,16</sup> use of different substrates,<sup>17</sup> and control of thin film thickness.<sup>18,19</sup>

Low-dimensional TI materials, such as nanoribbons and nanoplatelets (NPs), have arisen as an excellent alternative in order to overcome the impurity scattering effect, favoring the manifestation and access to the surface states in transport measurements due to their very large surface-to-bulk ratios,<sup>20,21</sup> which reduce bulk carrier contribution in TI electron transport. These unique nanostructures also stand out as excellent candidates for making functional devices easy to manipulate

and manufacture, creating an opportunity for versatile band structure engineering of the surface states.

To date, angle-resolved photoemission spectroscopy (ARPES) has been the predominantly used technique to determine TI band structure, employed mainly on TI thin films grown by MBE<sup>18,22,23</sup> and single-crystal samples cleaved in UHV conditions.<sup>4–7</sup> Some of these ARPES measurements, together with theoretical calculations, have revealed unconventional size effects like the evolution from 2D TI to 3D TI phase depending on film thicknesses in  $\text{Bi}_2\text{Te}_3$ <sup>23</sup> and  $\text{Bi}_2\text{Se}_3$ .<sup>18</sup> In contrast, STM and STS reports in TI crystals and MBE thin films<sup>4,5,24,25</sup> accessing local phenomena are less numerous than its momentum-resolved counterpart. Additionally, these studies have mainly focused on demonstrating the suppression of surface backscattering and the robust nature of MBE-grown TI systems.

Given the lack of STS measurements on TI nanostructures, we present in this work the first combined scanning tunneling microscopy (STM) and spectroscopy (STS) studies on high-quality epitaxial  $\text{Bi}_2\text{Te}_3$  nanoplatelets grown by vapor–solid process. Here we concentrate uniquely on the nanoscale spatial limit of topological insulators (nanoplatelets), where all dimensions are well below  $1 \mu\text{m}$ , in contrast to existing work in TI nanoplates.<sup>20,21</sup> We show that it is possible to tune the electronic properties of such high-quality TI nanomaterials

through its thickness, decreasing n-type charge carriers and local spatial electronic disorder as a function of thickness.

$\text{Bi}_2\text{Te}_3$  NPs were fabricated by a catalyst-free vapor transport and deposition process in a 12 in. horizontal tube furnace (Lindberg/Blue M) on HOPG substrate. The growth method is discussed in a previous work<sup>20</sup> (see Supporting Information, Figure S1 for details).

Although surface states of TIs are inherently robust against almost any surface modifications, these materials are prone to various surface chemical reactions, which are taken into account when preparing samples for devices and STM study. Particularly, continuous surface oxide growth has been observed in  $\text{Bi}_2\text{Te}_3$ <sup>26</sup> and  $\text{Bi}_2\text{Se}_3$ <sup>27</sup> after long exposure to oxygen-containing atmosphere, which causes a surface state degradation process after TI material interaction with the ambient environment. In our experiments the samples were transferred from the furnace to our STM chamber after exposure to air for just a few minutes. In order to remove the oxygen-containing layer adsorbed during transportation process (but do not change NP morphology), a few cycles of short sputtering at 200 eV were used followed by annealing at 130 C.

The final product is characterized by low temperature scanning tunneling microscopy and spectroscopy (Omicron LT-STM/STS). All topography scans were acquired in constant-current mode at 78 K in an ultrahigh vacuum chamber (pressure  $<10^{-10}$  Torr) with a sample bias between 0.3 and 1 V and tunneling currents between 1 and 20 pA.

STM topography images show NPs that usually exhibit triangular and hexagonal morphologies with lateral dimensions extending up to several micrometers. A group of triangular nanoplatelets is shown in Figure 1a with color-scale representing the topographic height. Blue regions highlight NPs, whereas earth tones correspond to HOPG. In general, NPs have different thicknesses, which enable us to investigate the thickness-dependent band structure of  $\text{Bi}_2\text{Te}_3$  NPs. Figure 1b shows a group of representative  $dI/dV$  spectra taken at the surface of NPs with different thicknesses.

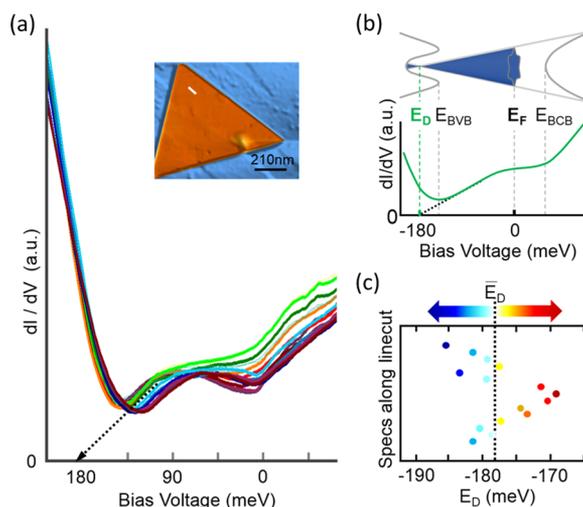
We resolve the atomic lattice of a  $\text{Bi}_2\text{Te}_3$  NP surface (Figure 1c) with a lattice constant of  $4.3 \pm 0.3$  Å (Figure 1d). A linecut taken across these NPs shows uniform thickness and flat surface in the majority of the platelet. NP height is 10 quintuple layers (QL) as determined by the height histogram. Determined NP height is always consistent with the  $\text{Bi}_2\text{Te}_3$  quintuple layer thickness. This correspondence suggests a quintuple layer-by-layer growth process for  $\text{Bi}_2\text{Te}_3$  nanoplatelets.

Additionally, evidence of van der Waals epitaxial growth was found (Figure 1a) in areas where terrace edges in the substrate aligned with NP edges (NP aligned in the same orientation on the substrate). Even though, for this highly lattice-mismatched system (2.7% compressive strain, Figure 1e) the present van der Waals interface drastically relaxes the lattice matching condition encountered in heteroepitaxial growth.<sup>28</sup> Growth conditions for this system are far from those used in MBE (delicate control of temperature and deposition rate), which make the observed van der Waals epitaxial growth in this system remarkable. This growth mode would indicate a high crystalline quality of as-grown NPs.

Figure 1f shows the NP thickness used for the present study. Raman spectra for the thinnest (8 QL) and the thickest (30 QL) NP are shown in Figure 1g.  $A_{1g}^1$  mode (out-of-plane mode at  $\sim 60$   $\text{cm}^{-1}$ ) and  $E_g^2$  mode (in-plane mode at  $\sim 102$   $\text{cm}^{-1}$ ) are broader in the thinnest NP, which could be attributed to a previously reported disorder-induced inhomogeneous broad-

ening and a stronger electron–phonon interaction with a concomitant reduction of phonon lifetime in TI nanostructures, which increases for thinner nanostructures.<sup>29–31</sup> Position of  $E_g^2$  vibrational mode does not show a significant change, which suggests that the frequency of in-plane vibrations is not very sensitive to changes in thickness, in contrast to  $A_{1g}^1$  and  $A_{1g}^2$  ( $\sim 132$   $\text{cm}^{-1}$ ) out-of-plane vibrational modes, which shift when reducing NP thickness.

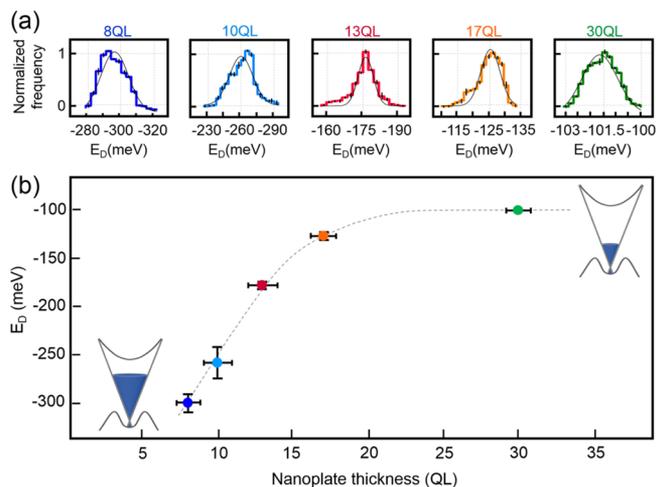
The spatial dependence of  $dI/dV$  spectra through a 50 nm linecut taken at 13 QL  $\text{Bi}_2\text{Te}_3$  NP surface is shown in Figure 2a,



**Figure 2.** Spatial variation snapshots of the local density of states of  $\text{Bi}_2\text{Te}_3$  nanoplatelets. (a) Measurements of  $dI/dV$  along a line of length 50 nm for a 13 QL. The zero-conductance point (intersection of black dashed line with 0 DOS) corresponds to the Dirac point ( $E_D$ ) of the wrapped topological surface state. (b) Schematic of surface band structure and  $dI/dV$  spectrum of  $\text{Bi}_2\text{Te}_3$  showing  $E_D$  and  $E_F$  positions. The position of the Dirac point for each spectrum is displayed in (c), where the dashed line corresponds to the mean  $E_D$  value for this nanoplatelet thickness.

providing the first glimpse of the spatial inhomogeneities and behavior analyzed in the rest of the letter. The Dirac energy ( $E_D$ ) of the TI surface state (SS) for each spectrum can be obtained at the intersection of the black dashed line (extension of linearly dispersing TI surface state wrapped in bulk valence band) with zero conductance line (Figure 2b). The variations of  $E_D$  along the linecut are shown in Figure 2c with values fluctuating below (in blue) and above (in red) the mean  $E_D$  value (178 mV for this NP thickness). These local spatial fluctuations have been explored before in STS studies of doped  $\text{Bi}_2\text{Te}_3$  crystals<sup>32,33</sup> and MBE thin films<sup>34</sup> but thus far never reported in a TI nanostructured system. Here we extend these measurements to the spatial limit.

The  $E_D$  variations for different NP thickness are quantified by the histograms seen in Figure 3a. A Gaussian has been fitted to each histogram to quantify the mean  $E_D$  value. The measured mean  $E_D$  values for different NP thickness are  $-301$  mV for 8 QL,  $-260$  mV for 10 QL,  $-178$  mV for 13 QL,  $-127$  mV for 17 QL, and  $-101$  mV for 30 QL, indicating that  $E_D$  shifts to less negative energies when nanoplatelet thickness increases (Figure 3b). Variations of the  $E_D$  value reach a minimum for the thickest NPs, where there is a 1.5% variation around the mean  $E_D$  value (see Figure S2 for details). This variation increases for thinner nanoplatelets reaching a 14% for 10 QL and 7.3% for 8 QL.



**Figure 3.**  $\text{Bi}_2\text{Te}_3$  nanoplatelet thickness dependence of  $E_D$  position. (a) Histogram of  $E_D$  obtained from STS results on 8, 10, 13, 17, and 30 QL  $\text{Bi}_2\text{Te}_3$  NPs at 78 K. A Gaussian has been fitted to each histogram to quantify fluctuations around the mean  $E_D$  value coming from STS spectra shifting. Slope variations of STS spectra are included as error bars in histograms. (b)  $E_D$  as a function of  $\text{Bi}_2\text{Te}_3$  nanoplatelet thickness obtained from histogram in (a) with corresponding error bar. As nanoplatelet thickness increases  $E_D$  shifts to less negative energies.

As revealed by these STS measurements there is a clear thickness dependence of  $E_D$  position, showing an evolution from a heavily doped n-type to lightly doped n-type behavior. The as-grown  $\text{Bi}_2\text{Te}_3$  compound has been reported to be either n- or p-type, depending on whether Te–Bi antisites or Te vacancies take the main role.<sup>22,35,36</sup> Both antisite defects (Te on Bi lattice and Bi on Te lattice) are energetically more favorable than possible vacancies in this material. However, only Bi-poor conditions ( $\text{Te}_{\text{Bi}}$ ) lead to n-type transport properties.<sup>37</sup> The observed evolution of charge carrier doping in this nano-

structured system might be a consequence of the reduction of  $\text{Te}_{\text{Bi}}$  antisite defects with  $\text{Bi}_2\text{Te}_3$  NP thickness increase.

To visualize spatial variations we map the  $E_D$  values as a function of sample thickness with spatial resolution down to 1 nm (Figure 4). The color scale represents variation (inhomogeneity) in Dirac point with respect to Fermi level, ranging from  $-322$  to  $-100$  mV in real space (as seen in the color scale bar below each map). Percentage variation maps with respect to the mean  $E_D$  value are shown in Figure S2. From our local spectroscopic measurements no insulating signatures (coming from the insulating bulk state) for any NP thickness were observed.

To quantify the characteristic length scales of the  $E_D$  spatial inhomogeneity for each NP thickness, the average spatial correlation function  $\langle G(\vec{r}) \rangle$ , and the angle-dependent spatial correlation function  $\langle G_\theta(\vec{r}) \rangle$  were computed for each  $E_D$  map (see Figures S3 and S4, respectively). The spatial autocorrelation function  $G(\vec{r})$  of an image (STM image or STS map in our case) is defined as the statistical correlation of any two points separated by a vector  $\vec{r} = \vec{r}_i - \vec{r}_j$  where  $\vec{r}_i$  and  $\vec{r}_j$  are the positions of those two points in the image.<sup>38,39</sup>

$$G(\vec{r}) = \frac{1}{N(\vec{r})} \sum_{i,j} \frac{(I_i - \langle I \rangle_1)(I_j - \langle I \rangle_2)}{\sigma_1 \sigma_2}$$

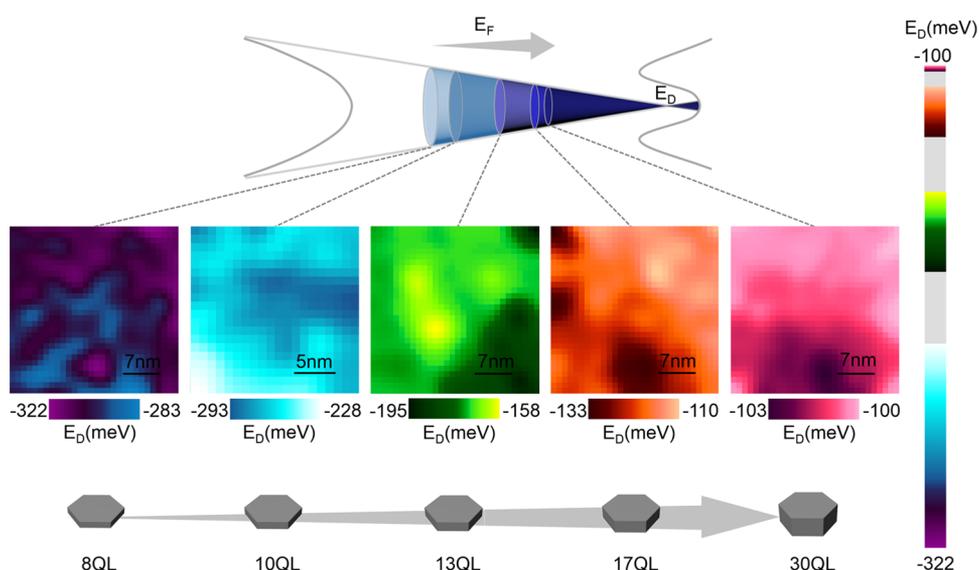
where

$$N(\vec{r}) = \sum_{i,j} \delta_{\vec{r}, (\vec{R}_i - \vec{R}_j)}$$

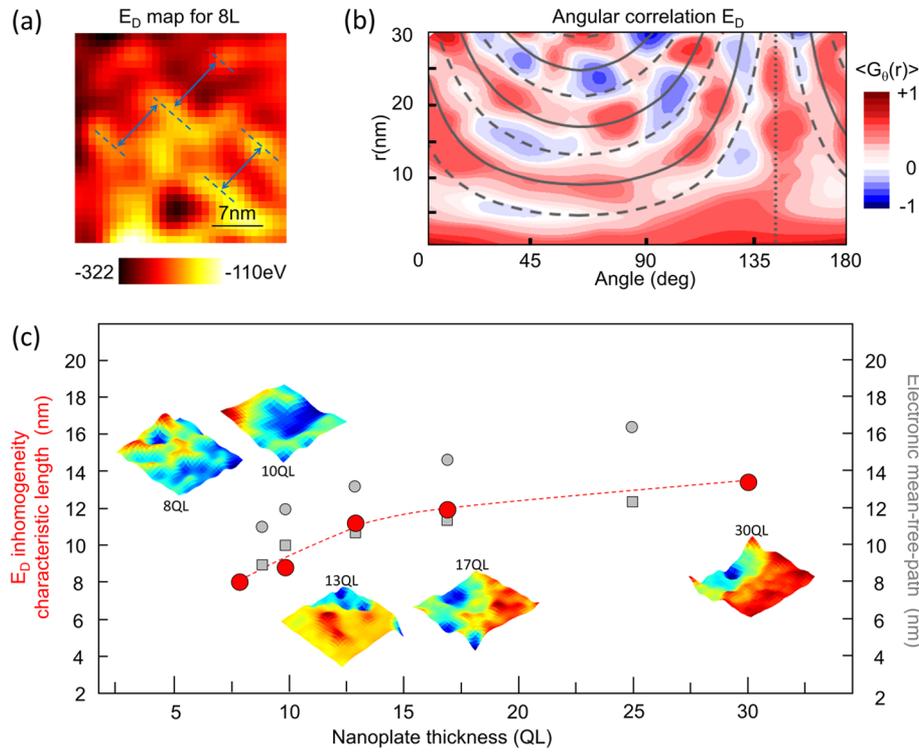
indicates the number of points at distance  $\vec{r} = \vec{R}_i - \vec{R}_j$ .

The average intensities (height value in an STM image or Dirac point value in an STS map) are calculated according to the expressions:

$$\langle I \rangle_1 = \sum_{i,j} \delta_{\vec{r}, (\vec{R}_i - \vec{R}_j)} I_i$$



**Figure 4.** Spatial dependence of  $E_D$  as a function of  $\text{Bi}_2\text{Te}_3$  nanoplatelet thickness. Map of spatial variations of the Dirac point, deduced from STS experiments for different  $\text{Bi}_2\text{Te}_3$  NP thicknesses. Maps for 8 QL, 13 QL, 17 QL, and 30 QL are  $30 \times 30 \text{ nm}^2$ , whereas for 10 QL is  $20 \times 20 \text{ nm}^2$ .  $E_D$  variations range from  $-322$  to  $-100$  mV, with  $E_D$  overall values approaching  $E_F$  as NP thickness increases. Corresponding  $E_D$  values are represented by the color scale bar below each map. The right color scale bar shows the entire  $E_D$  range.



**Figure 5.** Thickness dependence of  $E_D$  inhomogeneity characteristic length. (a) Real space 8 QL  $E_D$  map with guidelines (in blue) to highlight the observed repeating structure. (b) Angle-dependent correlation  $\langle G_\theta(\vec{r}) \rangle$  analysis for 8 QL  $E_D$  map clearly shows an arc pattern, which is consistent with the real space phase separation in  $E_D$  map (See Figure S4 for other thicknesses). (c) Characteristic length scale of observed  $E_D$  spatial inhomogeneity was obtained from angular correlation analysis of STS  $E_D$  maps.  $E_D$  maps for each thickness are included as 3D images. Bulk valence (gray squares) and conduction band (gray circles) mean free path versus thickness for fully diffuse surface scattering from ref 40 are also shown for comparison purposes.

$$\langle I \rangle_2 = \sum_{i,j} \delta_{\vec{r},(\vec{R}_i-\vec{R}_j)} I_j$$

And the standard deviations are calculated according to

$$\sigma_1^2 = \left( \frac{1}{N(\vec{r})} \sum_{i,j} \delta_{\vec{r},(\vec{R}_i-\vec{R}_j)} I_i^2 \right) - (\langle I \rangle_1)^2$$

$$\sigma_2^2 = \left( \frac{1}{N(\vec{r})} \sum_{i,j} \delta_{\vec{r},(\vec{R}_i-\vec{R}_j)} I_j^2 \right) - (\langle I \rangle_2)^2$$

The average spatial autocorrelation function  $\langle G(\vec{r}) \rangle$  is the result of averaging the correlation function of all vectors with the same magnitude  $|\vec{r}|$ . The angle-dependent autocorrelation function  $\langle G_\theta(\vec{r}) \rangle$  is the result of averaging the correlation function of all vectors with orientation  $\theta$  with respect to the horizontal axis and magnitude  $|\vec{r}|$ .

Both  $\langle G(\vec{r}) \rangle$  and  $\langle G_\theta(\vec{r}) \rangle$  of all the  $E_D$  maps reveal that there is a particular spatial pattern (with local minima and maxima), implying the presence of characteristic length scales for the observed spatial  $E_D$  inhomogeneity. The arcs in such pattern are imperfect, but repeat with a fixed periodicity, as clearly seen for the 8 QL map (Figure 5a,b), implying a pattern of phase separation of low and high carrier density domains over large length scales. The functional form of those arcs, for a system with partially disordered regions separated by a distance  $d$  and running along an angle  $\alpha$  with respect to the horizontal, measured at an angle  $\theta$ , is given by  $Nd/\cos((\alpha - 90^\circ) - \theta)$ <sup>41</sup> (see Figure S4 for details). For real space 8 QL  $E_D$  map (Figure

5a), guidelines (in blue) highlight the observed repeating structure, which is consistent with results from angle-dependent correlation  $\langle G_\theta(\vec{r}) \rangle$  analysis.

In addition, close to zero cross-correlation values between  $E_D$  maps and topographies for all NP thicknesses suggest that electronic order is disconnected from local structural disorder (Figure S3). These results provide evidence that the observed phase separation of the Dirac electrons in  $\text{Bi}_2\text{Te}_3$  NPs, which occurs in the form of stripe-like structures at repeat length  $d$ , may be self-organized. In contrast to electron–hole puddles in graphene<sup>42</sup> the  $E_D$  inhomogeneities observed here are actually spatially correlated with each other and to the nanoscale dimensions of the host material.

To further illustrate this point, the characteristic length scale  $d$  of such  $E_D$  spatial inhomogeneities obtained from  $\langle G_\theta(\vec{r}) \rangle$  analysis as a function of NP thickness is shown in Figure 5c.  $d$  values (red circles) increase with thickness, ranging from 8.2 to 13.5 nm. Electronic mean free path for bulk  $\text{Bi}_2\text{Te}_3$  are included for reference purposes. The observed length scale increase can be interpreted as a reduction of spatial electronic disorder for thicker nanoplatelets (probably connected to the decrease of  $\text{Te}_{\text{Bi}}$  antisite defects), which is in agreement with the observed broadening of Raman spectra for thinner nanostructures. Such decreases in spatial electronic disorder with thickness suggests that electron-disorder scattering gets stronger for thinner nanoplatelets. This is in agreement with the observed evolution of the system toward lightly n-type doping, which has been reported to be related to reduction in the electron–phonon interaction and electron-disorder scattering.<sup>37</sup>

In the same way, mobility has been reported to be increased linearly with TI thin film thickness and to be saturated as the samples got thicker,<sup>43</sup> following the same trend as the observed spatial electronic disorder behavior. In general, an increase in mobility is due to weak strain from the substrate and reduced defect density,<sup>43</sup> like the one displayed in this nanostructured system.

In conclusion we found in Bi<sub>2</sub>Te<sub>3</sub> nanoplatelets a clear thickness dependence of their topological surface state electronic properties. This leads to (1) the evolution from heavily n-type to lightly n-type surface doping as NP thickness increases, probably connected to a decrease in Te<sub>Bi</sub> antisite defects, which leads to higher quality thicker samples and (2) increase of length scale of phase separation of Dirac electrons with NP thickness, suggesting (together with Raman results) a reduction of electron-disorder scattering and electron–phonon interaction. Under these conditions an increase in mobility is expected.

Our results show a new approach for controlling the surface doping in TI nanostructured systems, which varies in thickness together with nanoscale phase separation of the surface state electronic structure. Recently, TI nanostructures have become a promising platform to explore both fundamental questions and applications related to low dimensionality of electronic systems. According to our results, the increase of n-type charge carrier density and electronic disorder as nanostructures get thinner (and approach the spatial limit) suggests that a good approach to tune Fermi level in these TI system is the use of moderate thickness samples. We expect our work will provide a new route for application of these nanostructured Dirac systems in electronic devices.

## ■ ASSOCIATED CONTENT

### Supporting Information

The Supporting Information is available free of charge on the ACS Publications website at DOI: 10.1021/acs.nanolett.6b03506.

- (i) Detailed description of Bi<sub>2</sub>Te<sub>3</sub> nanoplatelets growth method and resulting samples. (ii)  $E_D$  maps showing percentage variations with respect to mean  $E_D$  value. (iii) Autocorrelation and cross-correlation of topographies and  $E_D$  maps for all NP thickness. (iv) Angular correlation of  $E_D$  maps for all NP thickness (PDF)

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### Author Contributions

The manuscript was written through contributions of all authors. All authors have given approval to the final version of the manuscript.

### Notes

The authors declare no competing financial interest.

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